Table 1

Test Ref.	Al/Cr Ratio in Target	Crystal Structure	AI At%	Cr At%	Film Thickness [µm]	HV 0.03	·AV [m³m ⁻¹ N ⁻¹ 10 ⁻¹⁵]	Bond
A	3	B1	69.5	30.5	3.2	3100	0.8	HF1
В	3	B4	72	18	4.2	2100	1.0	HF1
С	1	B1	41.5	58.5	3.8	2800	1.5	HF1
D	0.33	B1	19	81	4.1	2300	2.5	HF1

Table 2

Test Ref.	Al/Cr Ratio In Target	P _{Target} [kW]	V _{substrate} [V]	P?? [Pa]	Temp [°C]			
Α	3	3	-50	3	450			
В	3	3	-50	1	450			
С	1	3	-50	3	450			
D	0.33	3	-50	3	450			

Table 3

Tubic o			
Substrate	AV [m³m ⁻¹ N ⁻¹ 10 ⁻¹⁵]		
Bias Voltage	[m³m⁻¹N⁻¹10⁻¹⁵]		
[M]	·		
0	1.23		
-20	0.47		
-40	0.76		
-100	0.83		
-150	1.0		
-200	1.36		

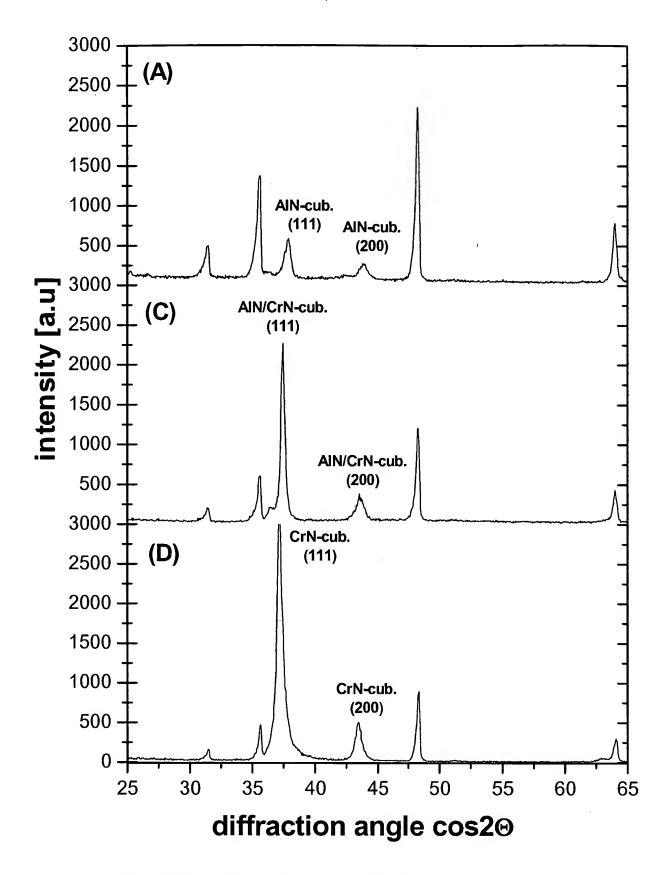
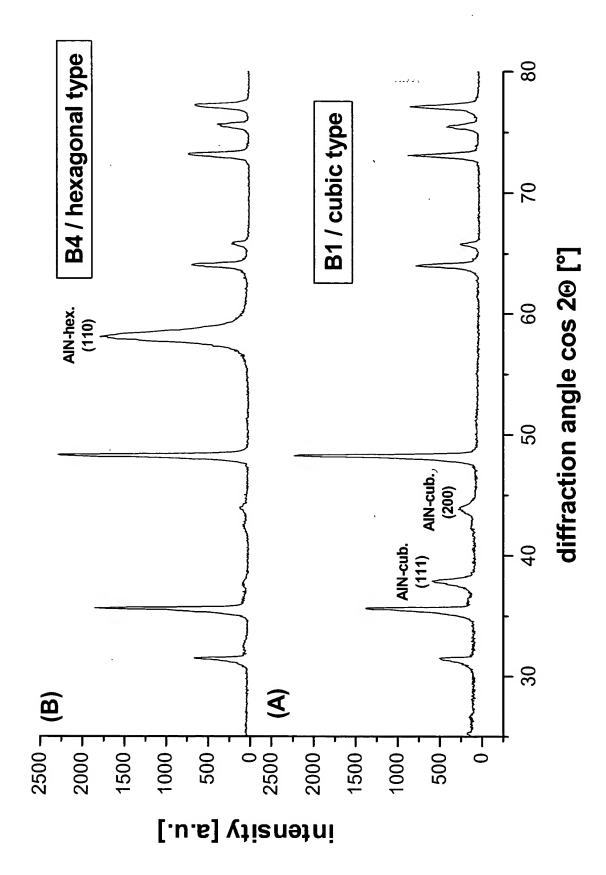


Fig. 2 - X-Axis: diffraction angle cos (2 theta), unit: degrees



Figada . X-Axis: diffraction angle cos (2 theta), unit: degrees